Abstract

IMPROVED POLISHING PADS AND METHODS FOR THEIR USE

An improved polishing pad is provided comprising a solid uniform polymer sheet (5) having no intrinsic ability to absorb or transport slurry particles having during use a surface texture or pattern which has both large (7) and small (6) flow channels present simultaneously which permit the transport of slurry across the surface of the polishing pad, where said channels are not part of the materials structure but are mechanically produced upon the pad surface. In a preferred version of the invention, the pad texture consists of a macrotexture produced prior to use and a macrotexture which is produced by abrasion by a multiplicity of small abrasive points at a regular selected interval during the use of the pad.

(Fig. 2)